

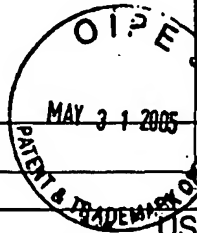
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**INFORMATION DISCLOSURE
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PTO/SS05A(10-01)
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Complete if Known	
Application Number	10/728,436
Filing Date	December 5, 2003
First Named Inventor	Chen, Yung-Tin
Group Art Unit	1756
Examiner Name	Unknown

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Attorney Docket No: MA-111

US PATENT DOCUMENTS

Examiner Initial *	Cite No	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date If Appropriate
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<i>AB</i>	A2	6523165	02/18/2003	Liu et al.			
<i>AB</i>	A3	6541165	04/01/2003	Pierrat			
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OTHER DOCUMENTS -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials *	Cite No	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
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Substitute Disclosure Statement Form (PTO-1449)

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